

Notice of References Cited

Application/Control No.

09/608,158

Applicant/Assignee Under
Reexamination

BALASINSKI ET AL.

Examiner

Kandasamy Thangavelu

Art Unit

2123

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U.S. PATENT DOCUMENTS

| * | | Document Number Country Code-Number-Kind Code | Date MM-YYYY | Name | Classification |
|---|---|--|-----------------|----------------|----------------|
| | A | US-6,470,489 | 10-2002 | Chang et al. | 716/21 |
| | B | US-6,453,452 | 09-2002 | Chang et al. | 716/8 |
| | C | US-6,096,457 | 08-2000 | Pierrat | 430/5 |
| | D | US-6,425,117 | 07-2002 | Pasch et al. | 716/21 |
| | E | US-6,261,724 | 07-2001 | Bula et al. | 430/5 |
| | F | US-6,223,139 | 04-2001 | Wong et al. | 703/5 |
| | G | US-6,263,299 | 07-2001 | Aleshin et al. | 703/5 |
| | H | US-6,453,274 | 09-2002 | Kamon | 703/2 |
| | I | US-6,301,697 | 10-2001 | Cobb | 716/19 |
| | J | US-6,383,719 | 05-2002 | Bula et al. | 430/312 |
| | K | US-5,866,935 | 02-1999 | Sogard | 257/435 |
| | L | US- | | | |
| | M | US- | | | |

FOREIGN PATENT DOCUMENTS

| * | | Document Number Country Code-Number-Kind Code | Date MM-YYYY | Country | Name | Classification |
|---|---|--|-----------------|---------|------|----------------|
| | N | | | | | |
| | O | | | | | |
| | P | | | | | |
| | Q | | | | | |
| | R | | | | | |
| | S | | | | | |
| | T | | | | | |

NON-PATENT DOCUMENTS

| * | | Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages) |
|---|---|---|
| | U | Sharan et al., "Panel: Subwavelength lithography: How will it affect your design flow?", IEEE June 1999. |
| | V | Kahng et al., "Subwavelength lithography and its potential impact on design and EDA", ACM, June 25, 1999. |
| | W | |
| | X | |

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.